

Appl No.: 10/665,339

Atty. Dkt. UCF-397CIP

Amendment to the Claims:

This listing of the claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

Claim 1 (Currently amended). A method of efficiently generating holograms having diffraction efficiency up to approximately 100% from photo-thermo- refractive (PTR) glasses, comprising the steps of:

providing a PTR glass blank having a total contamination with iron and heavy metals below 5 parts per million;

exposing the PTR glass blank with a UV light source or other source of ionizing radiation to create precursors of nucleation centers which are color centers and ions with changes in valence states;

exposing the UV exposed PTR glass blank containing precursors of nucleation centers with a high-power Visible light source greater than approximately 10 MW/cm² to decrease concentration of the precursors to decrease the rate of crystallization at the development stage thereby increasing a refractive index in the PTR glass after exposure to the visible light to record the hologram;

thermal treating the ~~UV and Visible light~~ exposed PTR glass ~~exposed to both the UV and high-power Visible~~ radiation to provide phase transformation depending on an amount and a power density of the high-power Visible radiation; and

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cooling the thermal treated PTR glass to room temperature to provide refractive index variations according to the amount and the power density of the high-power Visible radiation; and

restoring a the hologram from the exposed and thermal treated PTR glass by long wavelength radiation.

Claim 2 (Original). The method of claim 1, wherein the source of ionizing radiation is a UV light source.

Claim 3 (Original). The method of claim 2, wherein the step of exposing with UV light source includes a range of approximately 280 to approximately 350 nm.

Claim 4 (Original). The method of claim 2, wherein the step of exposing with the UV light source is approximately 325nm.

Claim 5 (Original). The method of claim 2, wherein the step of exposing with Visible light source includes a range of approximately 450 to approximately 600 nm.

Claim 6 (Original). The method of claim 2, wherein the step of exposing with a Visible light source includes; approximately 532 nm.

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Claim 7 (Original). The method of claim 1, wherein the step of exposing with a Visible light source includes: a high power source generating at approximately 10 megawatts/cm² to approximately 100 gigawatts/cm².

Claim 8 (Original). The method of claim 7, wherein the high power source generates at approximately 100 megawatts/cm².

Claim 9 (Original). The method of claim 7, wherein the high power source generates at approximately 10 gigawatts/cm².

Claim 10 (Original). The method of claim 1, wherein the step of generating a hologram includes the step of:

generating a simple hologram having substantially planar surfaces of equal refractive index.

Claim 11 (Original). The method of claim 1, wherein the step of generating a hologram includes the step of:

generating a complex hologram having substantially curved surfaces of equal refractive index.

Claim 12 (Original). The method of claim 1, wherein the step of thermal treating includes the step of:

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thermal treating the PTR glass in a temperature region ranging from approximately 480 to approximately 580°C for a period of from a few minutes to several hours appropriate for phase transformation.

Claim 13 (Currently amended). A method of generating optical components from photo-thermo-refractive (PTR) glasses, comprising the steps of:

providing a PTR glass blank having a total contamination with iron and heavy metals below 5 parts per million;

exposing the entire PTR glass blank with a UV light having a wavelength within the limits of the UV spectrum source to produce color centers;

exposing the UV exposed PTR glass with a high-power Visible light source for optical excitation of the color centers to partially bleach the color centers to record the hologram, the partial bleaching being non linear due to the high-power Visible light exposure;

thermal treating the UV and Visible light exposed PTR glass; and
cooling the thermal treated PTR glass to generate ~~generating an~~ a holographic optical component from the thermal treated PTR glass for a visible region.

Claim 14 (Currently amended). The method of claim 13, wherein the cooling step to generate ~~of generating~~ the optical component includes the step of:

generating the optical component from one of a lens or multi-lens objective, a combination of a prism or mirror with lenses, and a divergent/convergent beam splitter/combiner.

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Claim 15 (Currently amended). An optical element apparatus comprising:

a photo sensitive refractive (PTR) glass having photosensitivity to visible light caused by UV exposure to create color centers in the PTR glass, the PTR glass having a total contamination with iron and heavy metals below 5 parts per million;

means a visible light source for exposing the UV exposed PTR glass to Visible light greater than approximately 10 MW/cm² to increase a refractive index in the PTR glass for non linear bleaching of the color centers;

means for thermal treating the UV and Visible light treated PTR glass to fabricate a hologram or a phase plate from the PTR glass for a visible region, the hologram having a diffraction efficiency up to approximately 100%; and

means for using the PTR glass as one of a refractive and a diffractive volume holographic optical element based on modulation of a refractive index and an increment of refractive index, respectively.

Claim 16 (Currently amended). The optical element apparatus of claim 15, wherein the UV exposure includes a range of approximately 280 nm to approximately 350 nm.

Claim 17 (Currently amended). The optical element apparatus of claim 16, wherein the UV exposure is approximately 325 nm.

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Claim 18 (Currently amended). The ~~optical element~~ apparatus of claim 15, wherein the Visible light exposure includes a range of approximately 450 nm to approximately 600 nm.

Claim 19 (Currently amended). The ~~optical element~~ apparatus of claim 18, wherein the Visible light exposure is approximately 532 nm.

Claim 20 (Currently amended). The ~~optical element~~ apparatus of claim 15, wherein the thermal treatment means includes a range of approximately 480 to approximately 580°C for a period of from a few minutes to several hours appropriate for phase transformation.

Claim 21 (Currently amended). The ~~optical element~~ apparatus of claim 15, wherein the holographic optical element includes: a simple hologram having substantially planar surfaces of equal refractive index.

Claim 22 (Currently amended). The ~~optical element~~ apparatus of claim 15, wherein the holographic optical element includes: a complex hologram having substantially curved surfaces of equal refractive index.

Claim 23 (Currently amended). A method of generating refractive optical elements from photo-thermo- refractive (PTR) glasses, comprising the steps of:

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providing a PTR glass having a total contamination with iron and heavy metals below 5 parts per million;

exposing PTR glass with a source of ionizing radiation for generation of color centers;

exposing the UV exposed PTR glass with a high-power Visible light source for nonlinear partial bleaching of the color centers;

thermal treating the UV and Visible light exposed PTR glass for spatial modulation of a refractive index; and

restoring a hologram having up to approximately 100% diffraction efficiency from the thermal treated PTR glass.

Claim 24 (Original) The method of claim 23 wherein the source of ionizing radiation is a UV light source.

Claim 25 (Currently amended). The method of claim 23, wherein the refractive optical elements are lenses, waveguides, waveguide arrays, a multiplexer, demultiplexer and a combination multiplexer/demultiplexer mux/demux devices.

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